



Applied Materials Wins Semiconductor International Magazine's Best Product Award for SEMVision G2 FIB

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SANTA CLARA, Calif.--(BUSINESS WIRE)--July 7, 2005--Applied Materials, Inc. today announced that it is a recipient of Semiconductor International magazine's prestigious Editors' Choice Best Product Award for its Applied SEMVision(TM) G2 FIB system. The system revolutionized critical in-line defect root cause analysis by combining the industry's leading DR-SEM* system with on-board automated FIB* cross-sectioning capability that enabled chipmakers to review and physically analyze defects with a single production-line system.

"Continued advances in semiconductor technology have reshaped the world, and our Editor's Choice Product Awards program honors those products that have made those advances possible," said Pete Singer, Editor-in-Chief of Semiconductor International. "These products embody the very best of innovations on which chip makers rely to make their products smaller, faster, cheaper and more reliable. We congratulate the people and the companies that have had the insight and fortitude to bring these innovative products to the market."

"Receiving SI's Best Product award affirms the valuable contribution that the Applied SEMVision G2 FIB system has made to accelerate our customers' yield learning and production ramps," said Dr. Gilad Almogy, vice president and general manager of Applied Materials' Process Diagnostics and Control group. "The SEMVision G2 FIB provides breakthrough technologies that help solve critical bottlenecks in the fab. These systems have already been installed in virtually all advanced fabs worldwide, including 65nm-generation facilities."

With its patented ClearCut(TM) one-stop review and analysis technology, combining SEM, FIB and EDX (energy dispersive x-ray) capabilities on a single platform, the Applied SEMVision G2 FIB system offers full defect characterization that can identify the root cause quickly in order to prevent or minimize production defects. By performing high-speed, high-resolution automatic SEM review followed by FIB analysis of defects in just minutes, chipmakers can integrate this capability as part of their in-line review scheme. This unique capability enables a major step forward in production efficiency, yield and fab profitability.

Applied Materials (Nasdaq:AMAT), headquartered in Santa Clara, California, is the largest supplier of equipment and services to the global semiconductor industry. Applied Materials' web site is www.appliedmaterials.com.

Note(*): DR-SEM = defect review scanning electron microscope; FIB = focused ion beam

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